

ABSTRACT

A stamper with a sharp uneven pattern and a favorable surface state is obtained.

5 A photoresist master 100 is manufactured by forming a light absorption layer 103 and a photoresist layer 104, in that order, on top of a substrate 102, and then forming an uneven pattern 106 in the photoresist layer 104 by forming and developing a latent image, a Ni thin film 108 is formed on top of the uneven pattern 106 of the photoresist master 100 using
10 either a sputtering method or a vapor deposition method, a Ni film 110 is formed on top of the Ni thin film 108, and then the Ni thin film 108 and the Ni film 110 are separated from the photoresist master 100 to form a stamper 120.